

14 (Amended). A method according to claim 2 further comprising the step of:

carrying out a second heat treatment at a temperature of not lower than 900°C.

### **REMARKS**

Applicants appreciate the allowance of Claims 1, 2, 4-7, 9 and 11 in the above-identified application.

Applicants will now address the Examiner's remaining rejection.

#### **Double Patenting**

In the Office Action, the Examiner rejects Claims 3 and 13-14, "as well as 8, 10, 12" under 35 USC §101 as claiming the same invention as that of claims 3 and 1-2 and 8, 10, 12 of US Patent No. 6,335,231. This rejection is respectfully traversed.

Claim 3 of the present application does not claim the same invention as claim 3 of the '231 patent. In particular, Claim 3 of the present application recites the step of "patterning the single crystal semiconductor layer to form an active layer of a thin film transistor." Claim 3 of the '231 patent does not recite such a step. Hence, the claims are not claiming the same subject matter, and there is no double patenting. Further, as Claims 8, 10 and 12 of the present application are dependent on Claim 3 of this application, these claims should also not be rejected for double patenting

Claims 13 and 14 have been amended herein as follows "carrying out a second heat treatment at a temperature of [900 to 1200] not lower than 900°C." Hence, these claims do not have the same

recitations as in claims 1 and 2 of the '231 patent. This should overcome the double patenting rejection.

For at least the above-stated reasons, it is respectfully submitted that the claims of the present application should not be rejected for double patenting. Accordingly, it is requested that this rejection be withdrawn, and the claims allowed.

#### IDS

Applicant is submitting an IDS herewith. It is respectfully requested that this IDS be entered and considered prior to the issuance of any further action on this application.

#### Conclusion

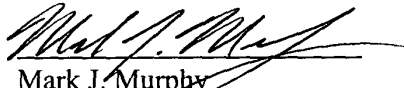
For at least the above-stated reasons, it is respectfully submitted that the present application is now in a condition for allowance.

If any further fee is due for this application, please charge our deposit account 50/1039.

Favorable reconsideration is earnestly solicited.

Respectfully submitted,

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Marked-up copy of the amendments made herein:

**IN THE CLAIMS:**

Please amend the claims as follows:

13 (Amended). A method according to claim 1 further comprising the step of:

carrying out a second heat treatment at a temperature of [900 to 1200] not lower than

900°C.

14 (Amended). A method according to claim 2 further comprising the step of:

carrying out a second heat treatment at a temperature of [900 to 1200] not lower than

900°C.